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Attorney Docket No.: 5308-412

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re: Saxler

Confirmation No.: 6346

Application No.: 10/849,589

Group Art Unit: 2811

Filed: May 20, 2004

Examiner: Wael M. Fahmy

For: SEMICONDUCTOR DEVICES HAVING A HYBRID CHANNEL LAYER, CURRENT APERTURE TRANSISTORS AND METHODS OF FABRICATING SAME

Date: August 24, 2004

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. § 1.97(b)

Sir:

Attached is a list of documents on Form PTO-1449, together with a copy of any listed foreign patent document and/or non-patent literature. A copy of any listed U.S. patent and/or U.S. patent application publication is not provided herewith in accordance with the waiver by the U.S. Patent and Trademark Office of requirements under 37 C.F.R. § 1.98(a)(2)(i) for all U.S. national patent applications filed after June 30, 2003 and for all international applications that have entered the national stage under 35 USC § 371 after June 30, 2003.

It is requested that these documents be considered by the Examiner and officially made of record in accordance with the provisions of 37 C.F.R. § 1.56 and Section 609 of the MPEP.

This Information Disclosure Statement is submitted in accordance with 37 C.F.R. § 1.97(b), within three months of the filing date of the above-referenced application or before the mailing of a first Office Action on the merits, whichever event occurs last. Therefore, no fee is believed due. However, the Commissioner is hereby authorized to charge any deficiency or credit any overpayment to Deposit Account No. 50-0220.

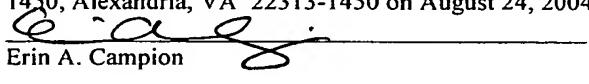
Respectfully submitted,


Elizabeth A. Stanek
Registration No. 48,568

Myers Bigel Sibley & Sajovec, P.A.
P. O. Box 37428
Raleigh, North Carolina 27627
Telephone: (919) 854-1400
Facsimile: (919) 854-1401
Customer No. 20792

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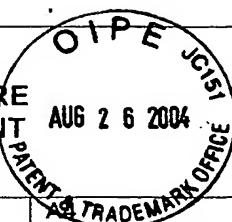
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Erin A. Campion

INFORMATION DISCLOSURE
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Sheet A1 of

U.S. PATENTS AND PATENT PUBLICATIONS

Examiner Initials*	Cite No.	U.S. Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY
		Number	Kind Code (if known)		
	1.	Re. 34,861		Davis et al.	02-14-1995
	2.	6,639,255		Inoue et al.	10-28-2003
	3.	6,586,781		Wu et al.	07-01-2003
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	46.	6,686,261		Gehrke et al.	02-03-2004
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Group Art Unit	2811
Examiner Name	Wael M. Fahmy

Sheet A2 of A4 Attorney Docket Number 5308-412

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		Number	Kind Code (if known)		
	53.	6,570,192		Davis et al.	05-27-2003
	54.	6,545,300		Gehrke et al.	04-08-2003
	55.	6,521,514		Gehrke et al.	02-18-2003
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Examiner Initials*	Cite No.	Foreign Patent Document			Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	T
		Office	Number	Kind Code (if known)			
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	66.	JP	2002016087	A	NEC Corp	01-18-2002	Abstract
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Substitute form 1449A/PTO				Complete if Known	
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	84.	Gradecak, "Microscopic Evidence of Point Defect Incorporation in Laterally Overgrown GaN," <i>Applied Physics Letters</i> . Vol. 80, No. 16, pp. 2866-2868 (2002).	
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	100.	Sullivan et al. "High-Power 10-GHz Operation of AlGaN HFET's on Insulating SiC," <i>IEEE Electron Device Letters</i> . Vol. 19, No. 6, pp. 198-200 (June 1998).	
	101.	Wagner et al. "Influence of the Carrier Gas Composition on Morphology, Dislocations, and Microscopic Luminescence Properties of Selectively Grown GaN by Hydride Vapor Phase Epitaxy," <i>Journal of Applied Physics</i> . Vol. 92, No. 3, pp. 1307-1316 (2002).	
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	105.	United States Patent Application entitled "Co-Doping for Fermi Level Control in Semi-Insulating Group III Nitrides," filed January 7, 2004 (Attorney Docket No. 5308-371).	
	106.	United States Patent Application entitled "Nitride Heterojunction Transistors Having Charge-Transfer Induced Energy Barriers and Methods of Fabricating the Same," Serial No. 10/772,882, filed February 5, 2004 (Attorney Docket No. 5308-389).	
	107.	United States Patent Application entitled "Nitride-Based Transistors with a Protective Layer and a Low-Damage Recess and Methods of Fabrication Thereof," Serial No. 10/758,871, filed January 16, 2004 (Attorney Docket No. 5308-291).	
	108.	United States Patent Application entitled "Methods of Fabricating Nitride-Based Transistors with a Cap Layer and a Recessed Gate," filed July 23, 2004 (Attorney Docket No. 5308-392).	

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	109.	United States Patent Application entitled "Nitride-Based Transistors and Methods of Fabrication Thereof Using Non-Etched Contact Recesses," Serial No. 10/617,843, filed July 11, 2003 (Attorney Docket No. 5308-248).	
	110.	United States Patent Application entitled "Methods of Having Laterally Grown Active Region and Methods of Fabricating Same," filed July 26, 2004 (Attorney Docket No. 5308-374).	
	111.	United States Patent Application entitled "Methods of Fabricating Nitride-Based Transistors Having Regrown Ohmic Contact Regions and Nitride-Based Transistors Having Regrown Ohmic Contact Regions," Serial No. 10/849,617, filed May 20, 2004 (Attorney Docket No. 5308-413)	
	112.	United States Patent Application entitled, "Silicon Carbide on Diamond Substrates and Related Devices and Methods," (Cree Docket No. P0387).	

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